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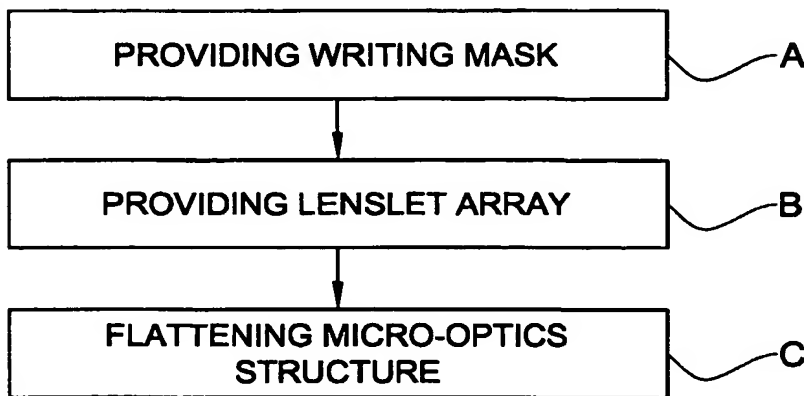
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(54) Title: **METHOD FOR PRODUCTION OF MICRO-OPTICS STRUCTURES**



(57) Abstract: A novel method for fabricating a micro-optics structure, having at least one lenslet array, is presented. A writing mask is provided being configured in accordance with an arrangement of the lenslet array to be manufactured. The writing mask is applied to a structure formed by a photosensitive layer of a predetermined thickness carried by a substrate, and the photosensitive layer is exposed through the writing mask using a predetermined spectral range of the exposure and a predetermined distance between the mask and said photosensitive layer, to thereby pattern the photosensitive layer through a

diffraction optical element of said mask. The so-obtained pattern is in the form of optical nonhomogeneities in the photosensitive layer material, defining the lenslet array within the photosensitive layer.